

Advancements in Understanding Plasma Cleaning

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Outline

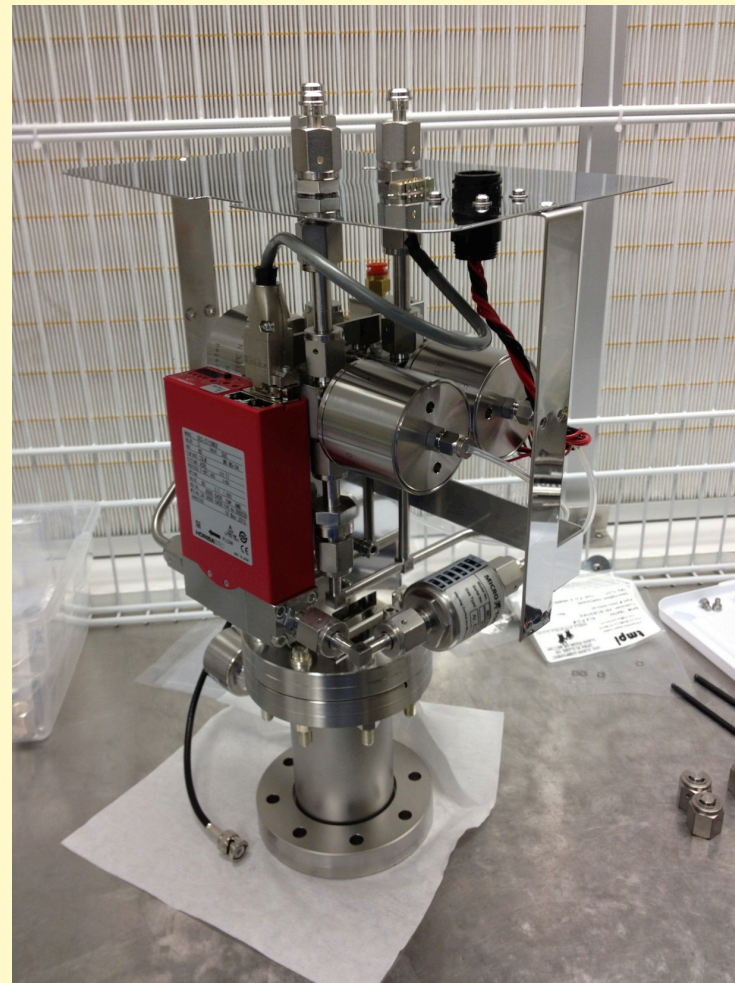
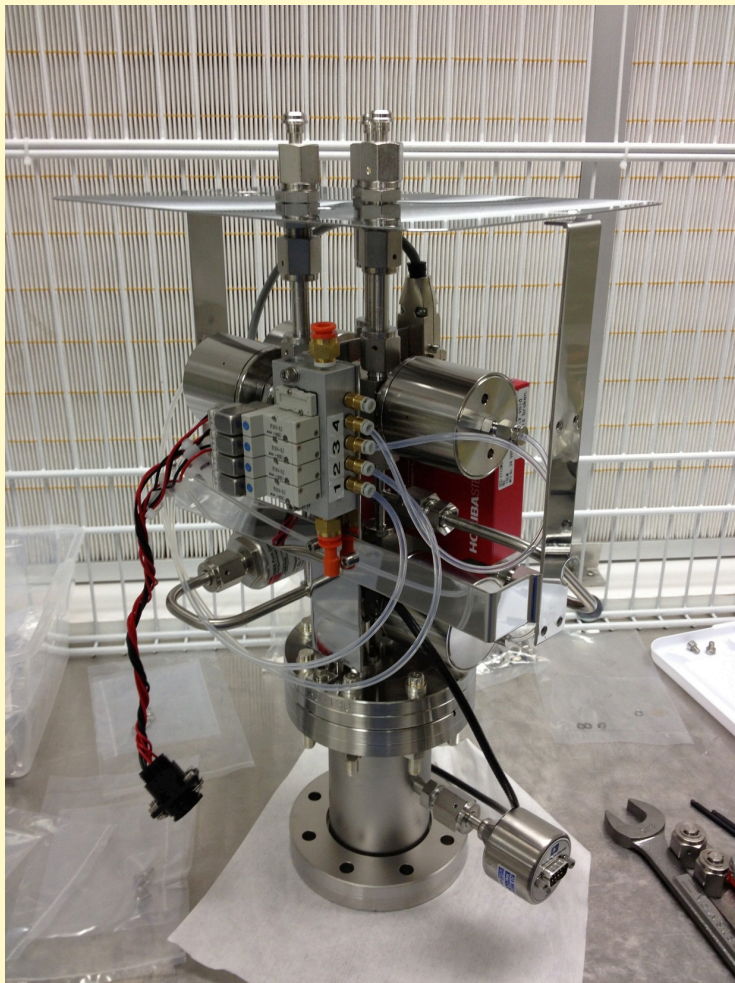
- EUV-compatible plasma system
- Cleaning Rate Metrology
- Parametric study
- H₂ Plasma Effects on Materials
- Future Directions
- Conclusions



Background and motivation

- Ru-capped MLMs oxygen sensitive
- Established that cleaning needs to be H₂ based
- Prior XEI efforts at plasma cleaning for EUV used inappropriate materials/methods
- Partnered with SEMI equipment OEM to develop advanced plasma cleaning system
- Delivered April '13, passed initial cleanliness analyses, more detailed studies underway

EUV-compatible plasma system

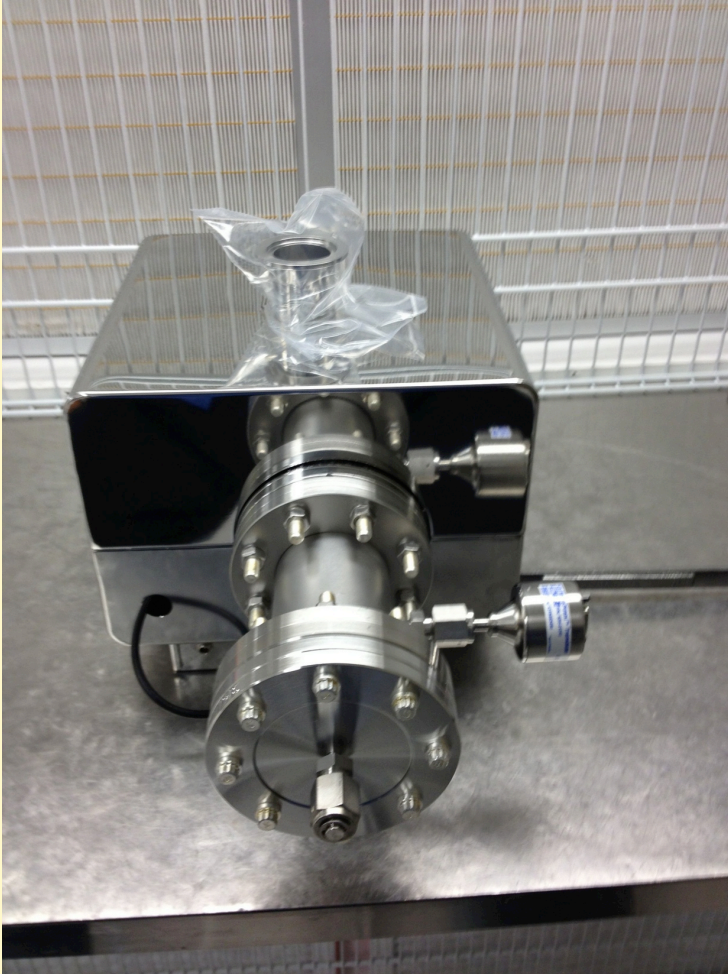


Details available at poster session P28



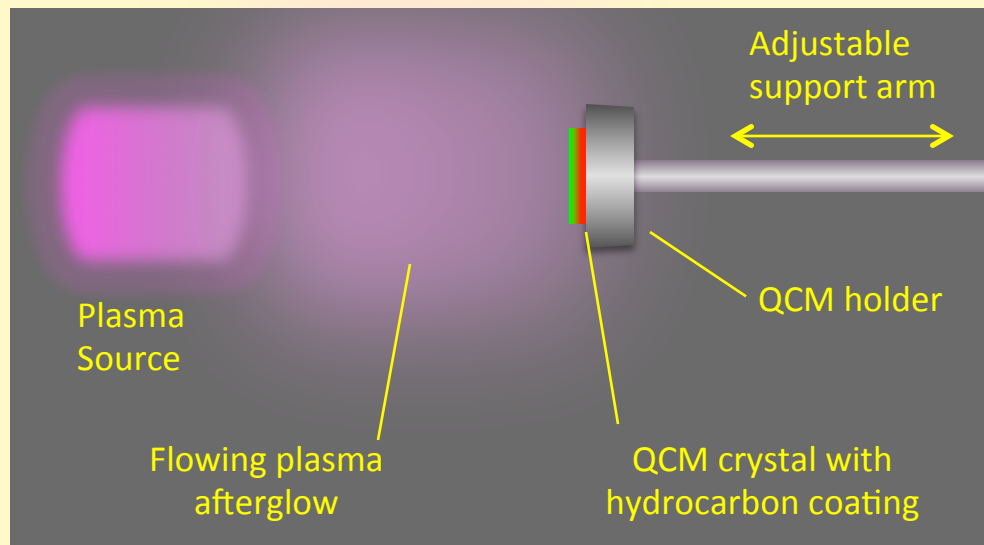
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EUV-COMPATIBLE PLASMA SYSTEM



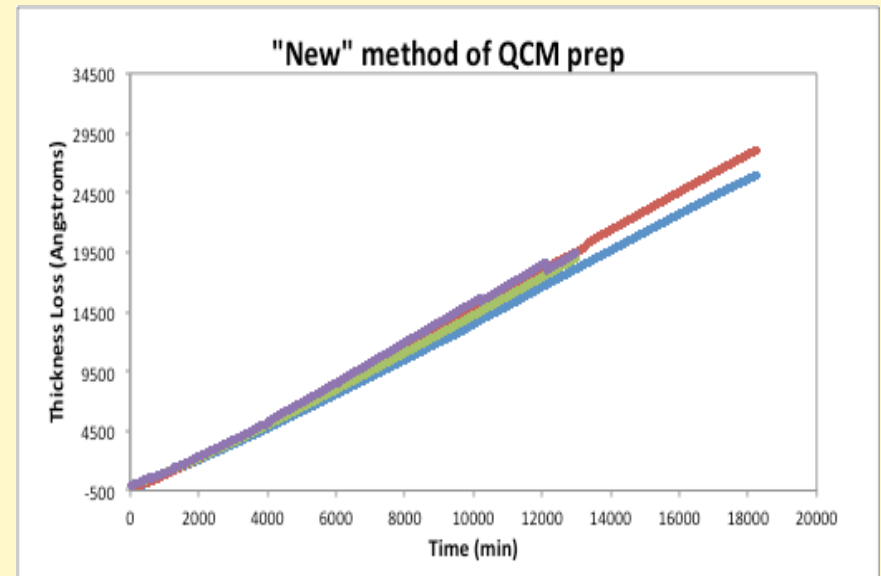
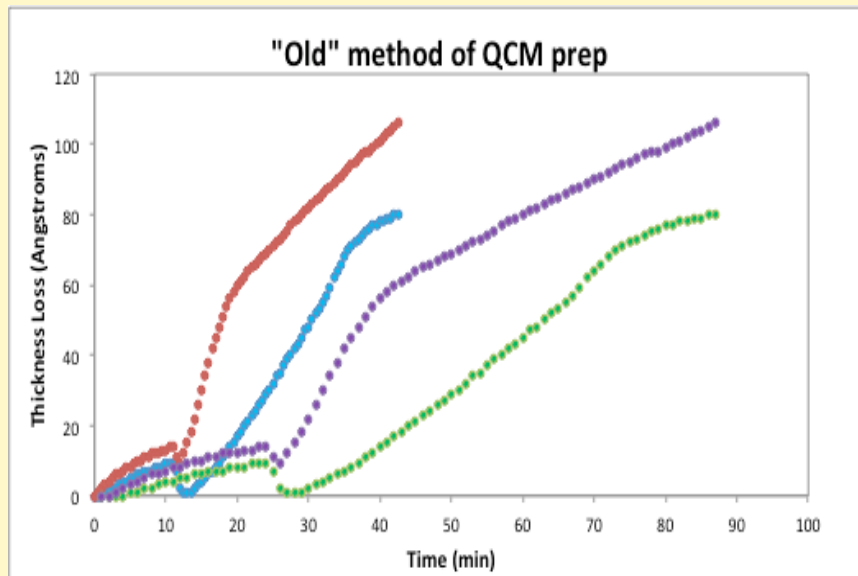
Quantifying Plasma Cleaning

- Difficult to optimize design of plasma and process without quantitative metric
- Hydrocarbon (HC) contamination varies: composition, carbon bonding (type, density), extent of polymerization
- Solution:
 - Use established quartz crystal microbalance (QCM) tools
 - Devise reproducible deposition of hydrocarbon-based solid film on QCMs
 - Plasma clean HC, record $\Delta(\text{thickness})$ vs. time to estimate cleaning rate

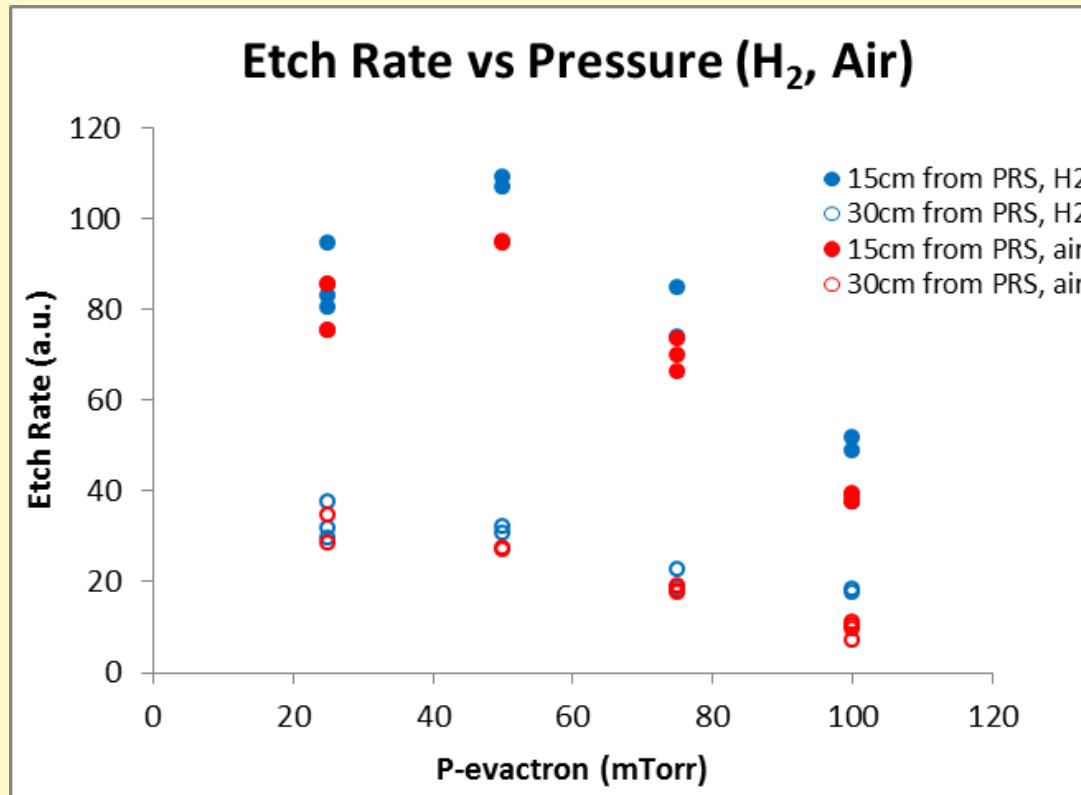


Quantifying plasma cleaning

- Needed to develop process for deposition of hydrocarbon proxy with inter- and intra-sample repeatability
- Need is stability for plasma cleaning process development- practical cleaning rates will vary



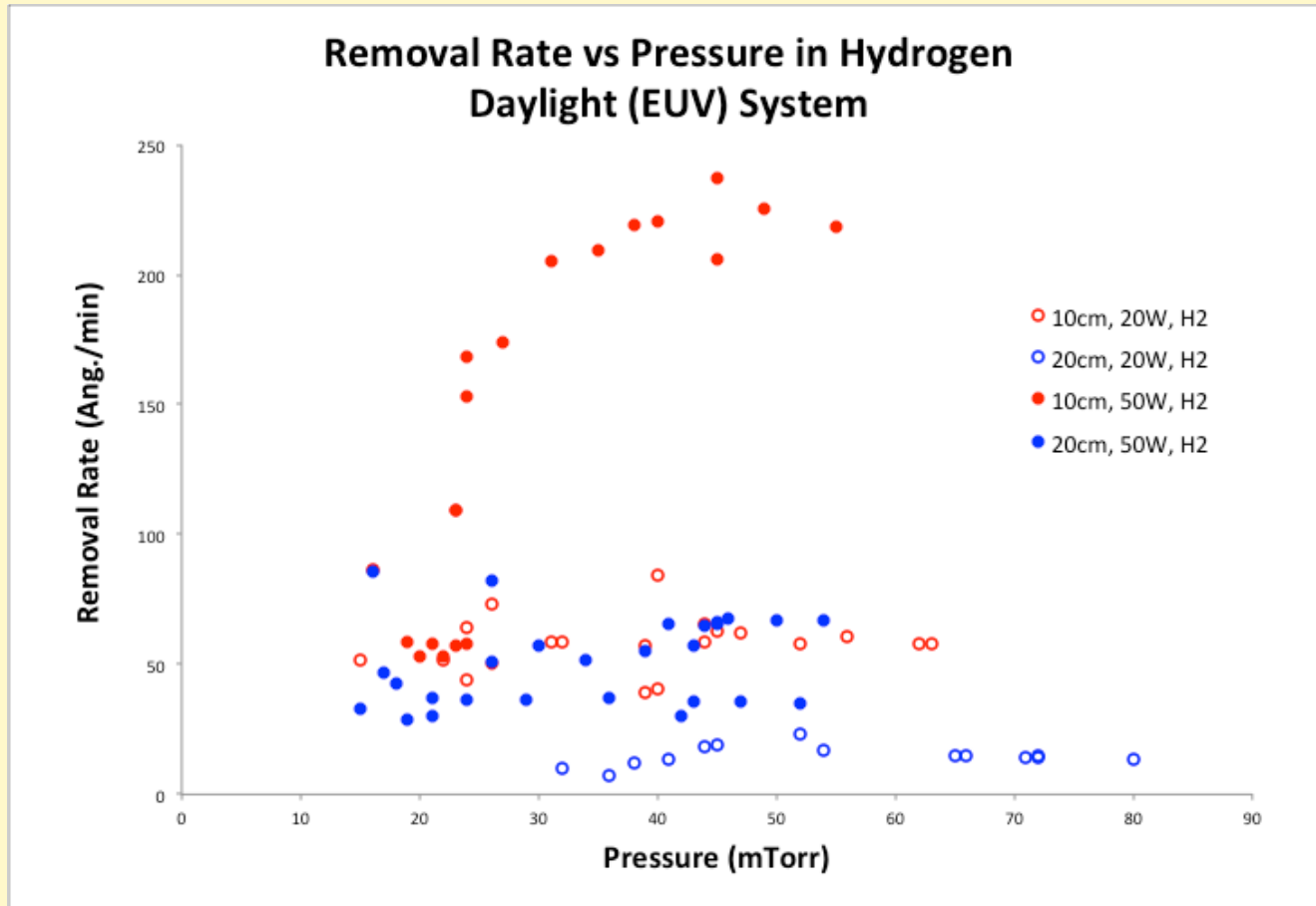
Removal rates standard Evactron



Measured in 10 liter chamber



Removal rates Daylight system



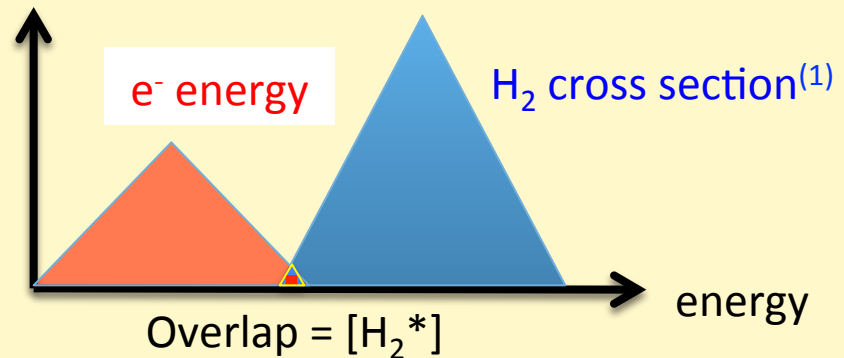
For this chamber (two 6"CF crosses) and pumping combination:

- < 30 mTorr appears to deplete reactant feedstock
- Cleaning rate more than linear with plasma power

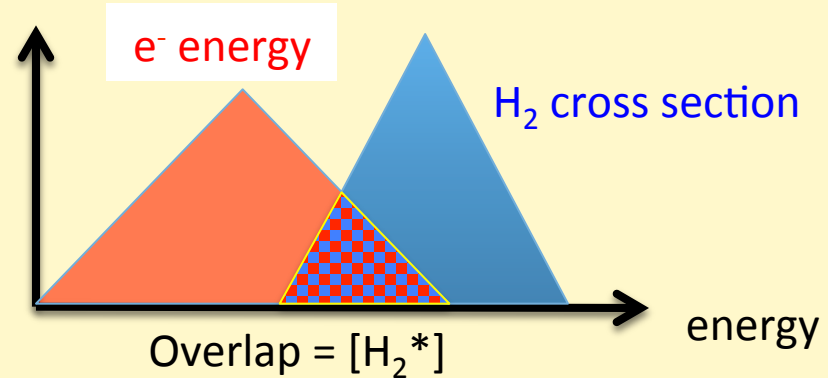


Cleaning rate dependence on plasma power

- Radical production is result of overlap of electron energy and excitation cross section



- But double power and both # and energy of e⁻ go up



Chamber geometry effects

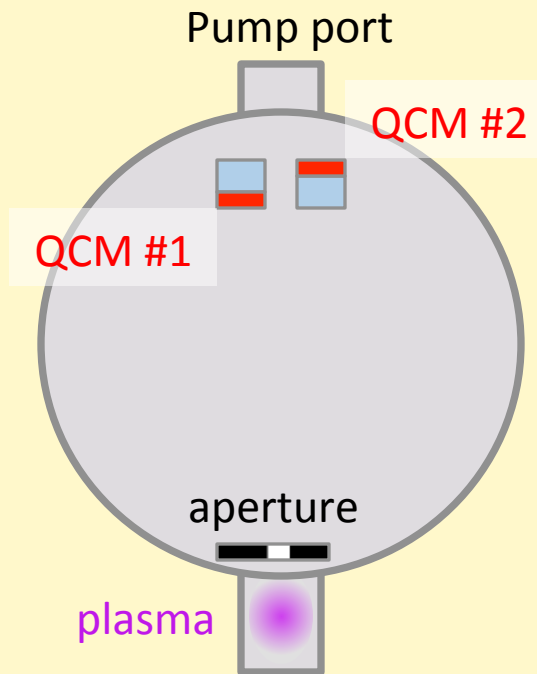
Comparing data from last two data slides:

- 10 ℓ chamber, 50 mTorr, 20 W:
 - 110 Å/min. @ 15 cm away
 - 30 Å/min. @ 30 cm away
- 30 ℓ chamber (CF crosses), 50 mTorr, 20 W:
 - 15 Å/min. @ 20 cm away

➔ Chamber volume/features, pumping, transport vector play a strong role in cleaning



Pressure and geometry effects: an example

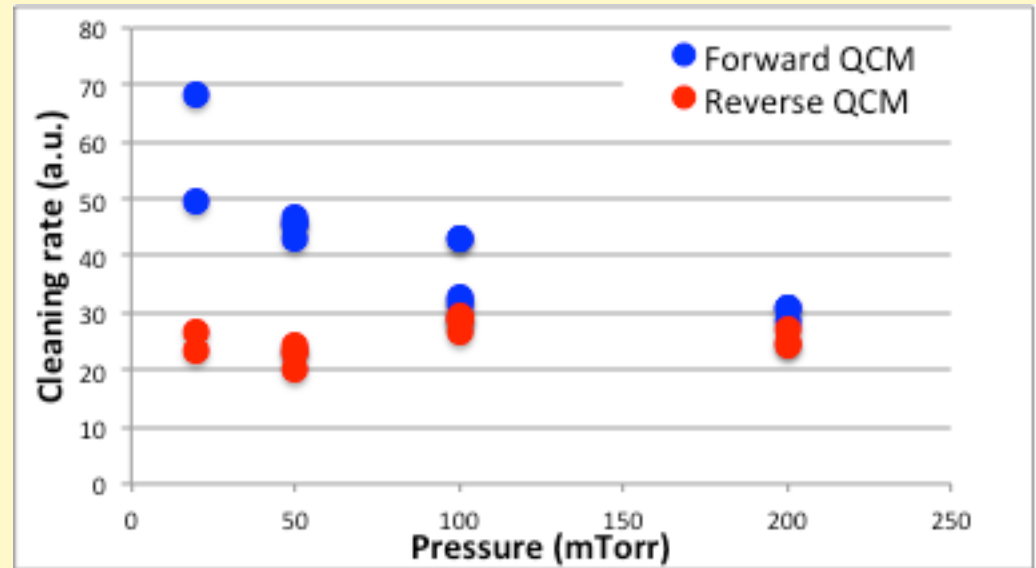


- 10 litre chamber
- 2 QCMs
 - One facing plasma
 - One facing pump port
- Aperture to optionally constrict plasma effluent
- Measured cleaning rates at different pressures

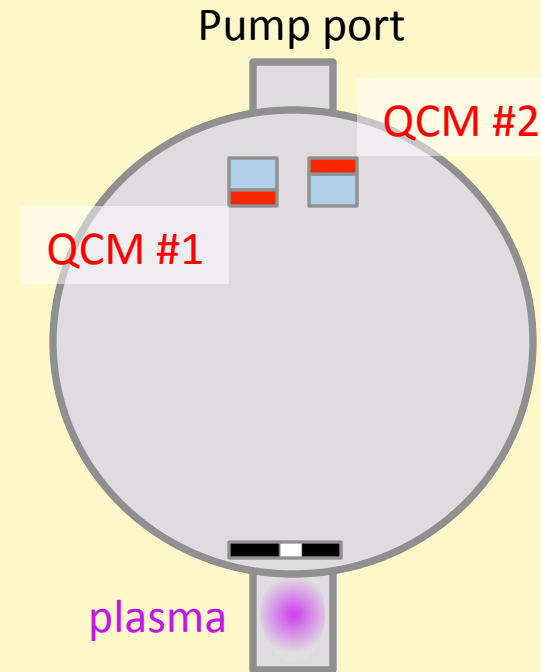
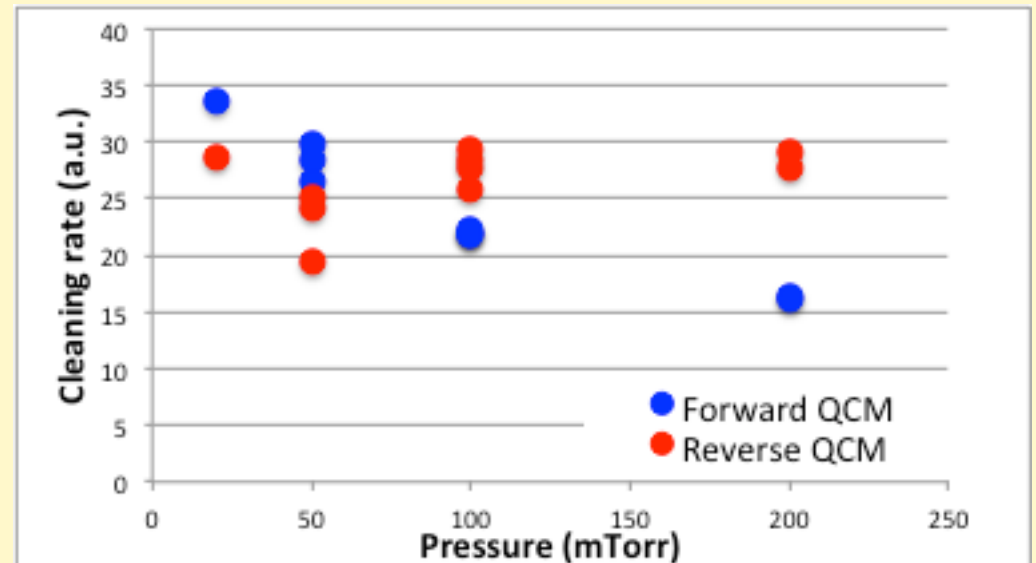


Pressure and geometry effects: an example

Apertured



Open

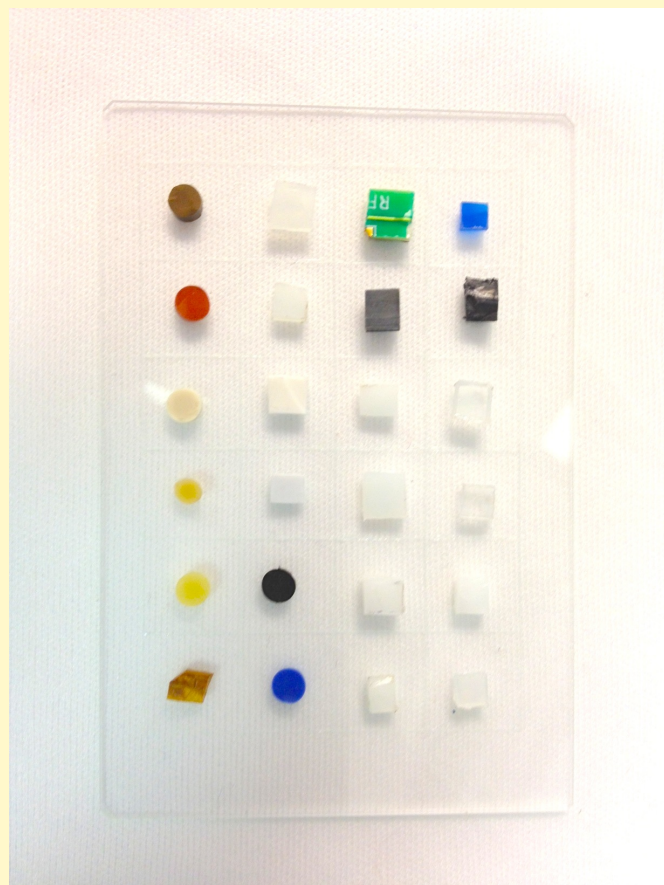


Study of plasma effects on various materials

- Frequent area of concern: how does plasma cleaning affect other materials?
- To address this question, samples of 36 materials were collected and then mounted on glass slides
- Materials included common plastics/polymers, lubricants, and o-rings
- Fixing of some samples performed using cyanoacrylate glue; lubricants applied through mask to form 6 mm x 0.1 mm disk



Study of H₂ plasma effects on various materials



- **Lubricants**

Krytox

6300

Apezion-L

6200

C5-A

OC Seven

Braycote 1632

- **O-ring materials**

Viton

Low-fill Viton

Buna nitrile

Silicone

Fluorosilicone

Kalrez 8085

Vespel

Kalrez ultrapure

- **Plastics/polymers**

ABS

PTFE

Plexiglas

Delrin 127UV, 100P, 527UV

PVDF

Polycarbonate

HDPE

UHMW-P

Polypropylene

PVC

Acrylic

Nylon

PEEK

EPDM

- **Others**

Kapton (tape)

Teflon (tape)

FR-4 (PCB)

Dupont

Loctite

Nye

Parker

MPT

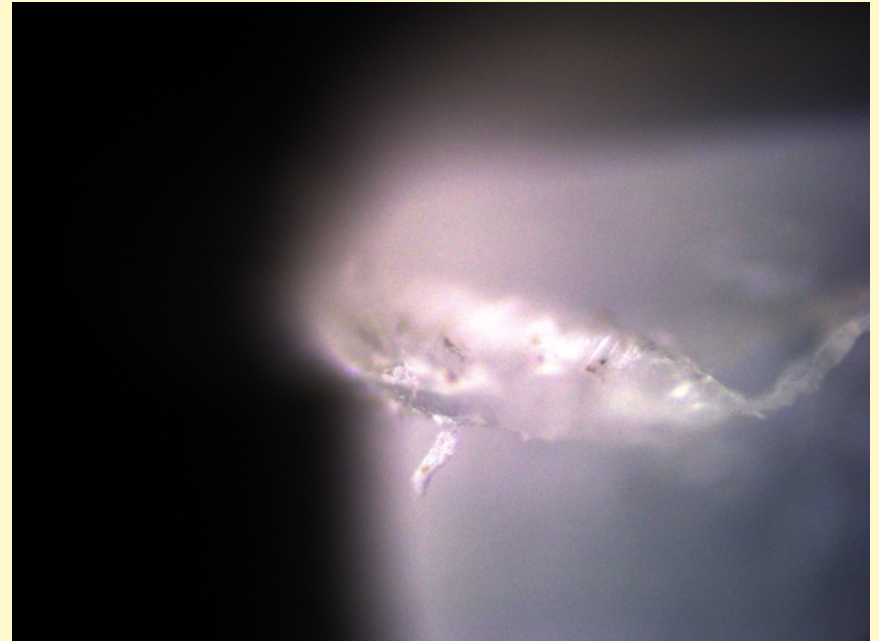
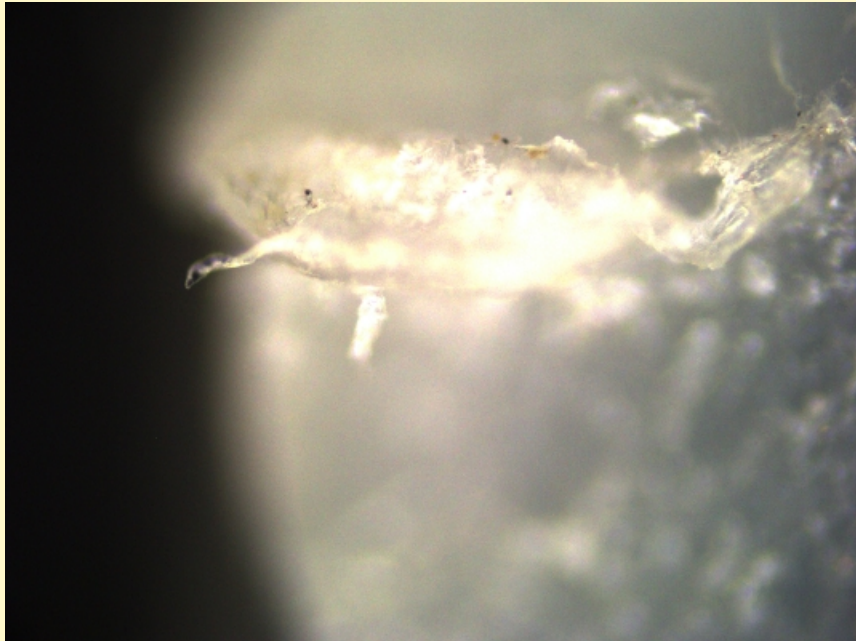
Gore



Study of plasma effects on various materials

- 2 hrs. of H₂ plasma @ 50 Watts
- All images 100x

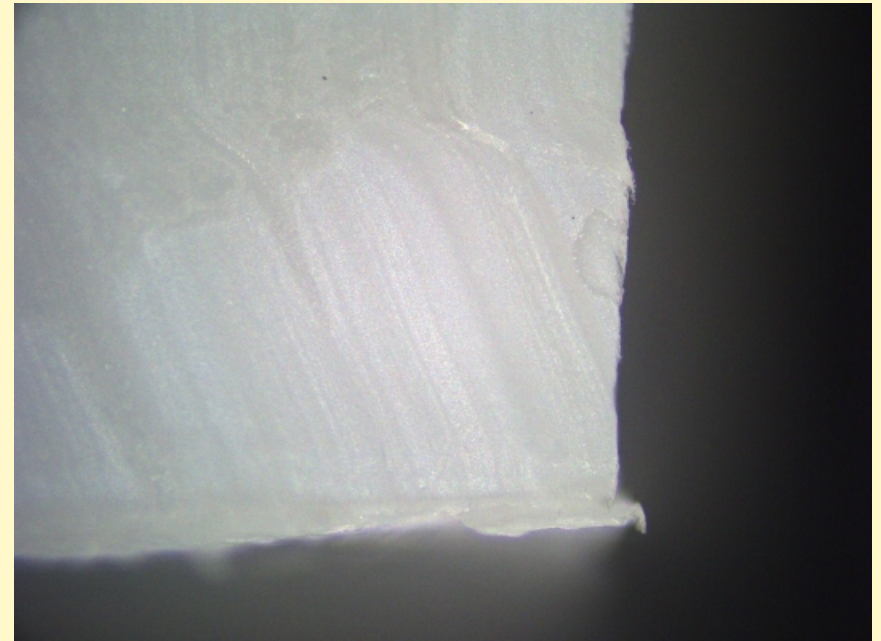
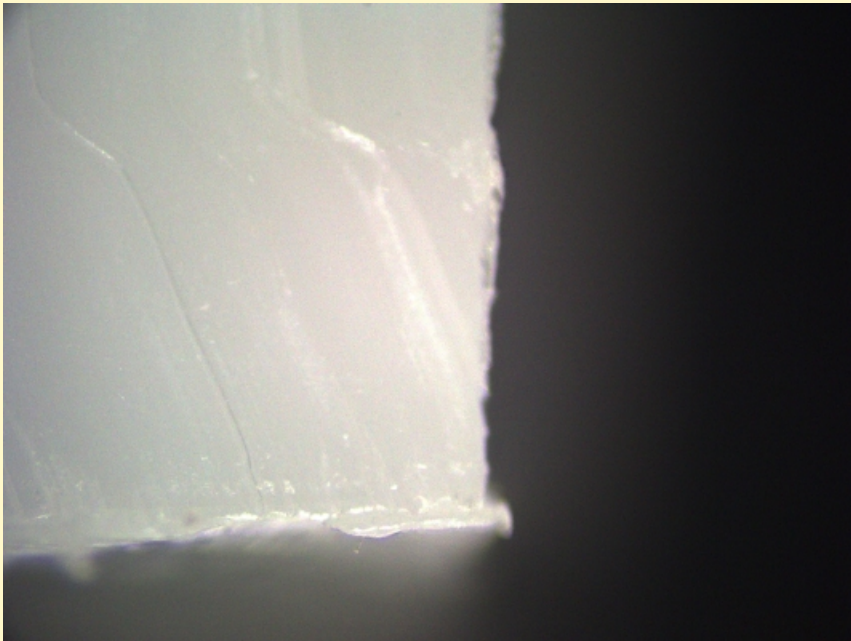
Acrylic



Study of plasma effects on various materials

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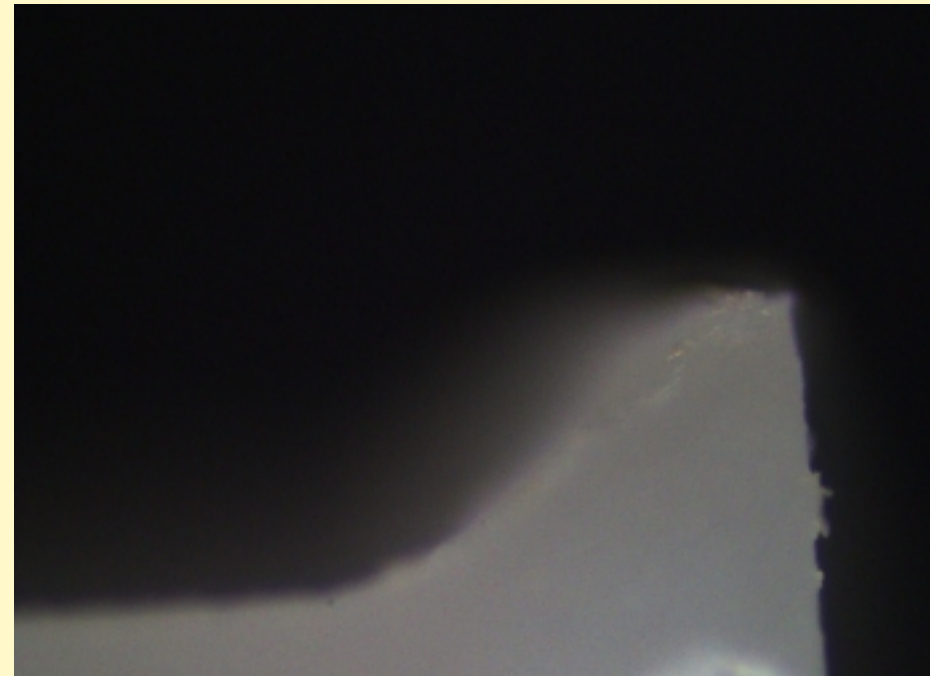
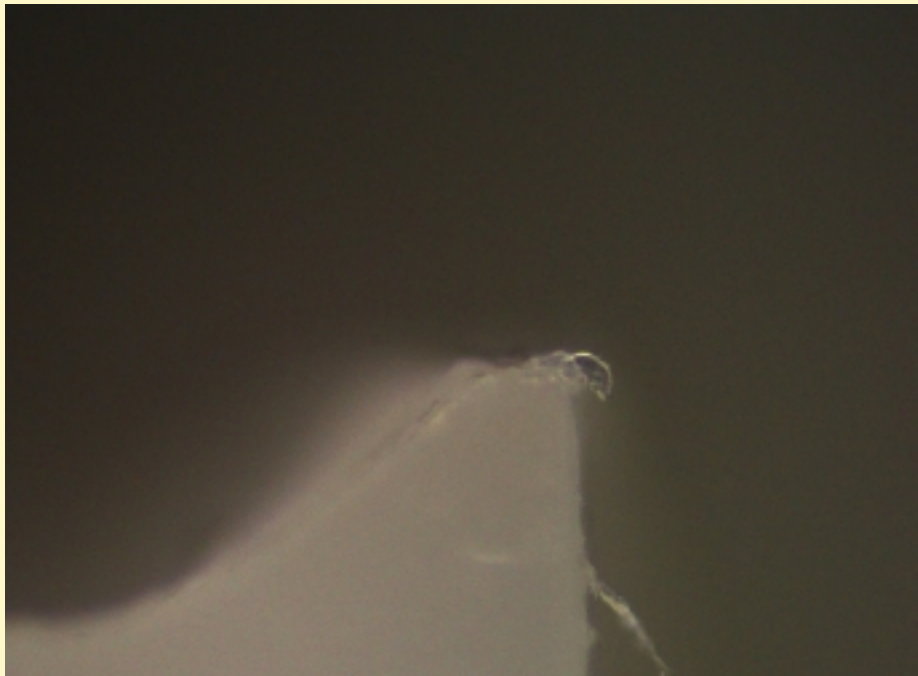
Nylon



Study of plasma effects on various materials

- 2 hrs. of H₂ plasma @ 50 Watts
- All images 100x

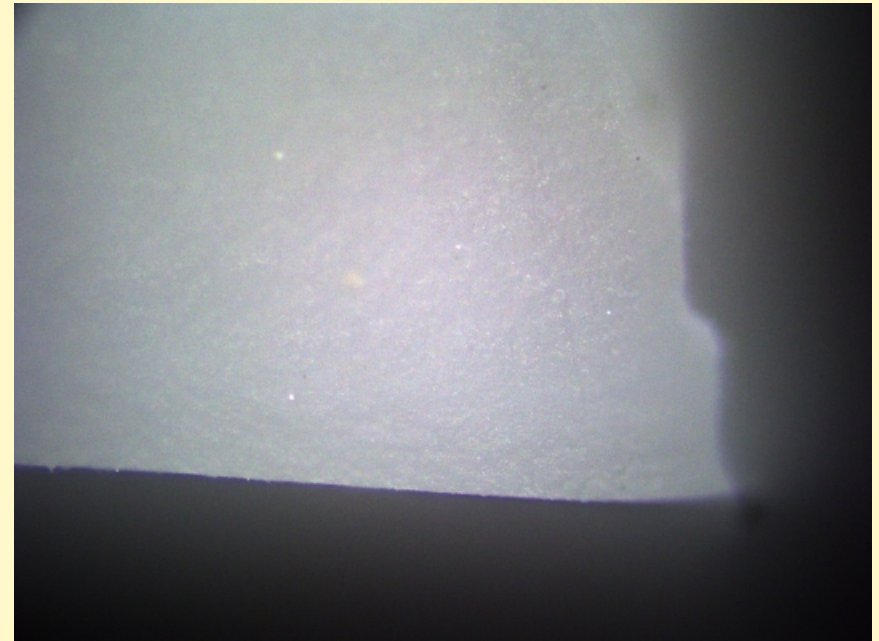
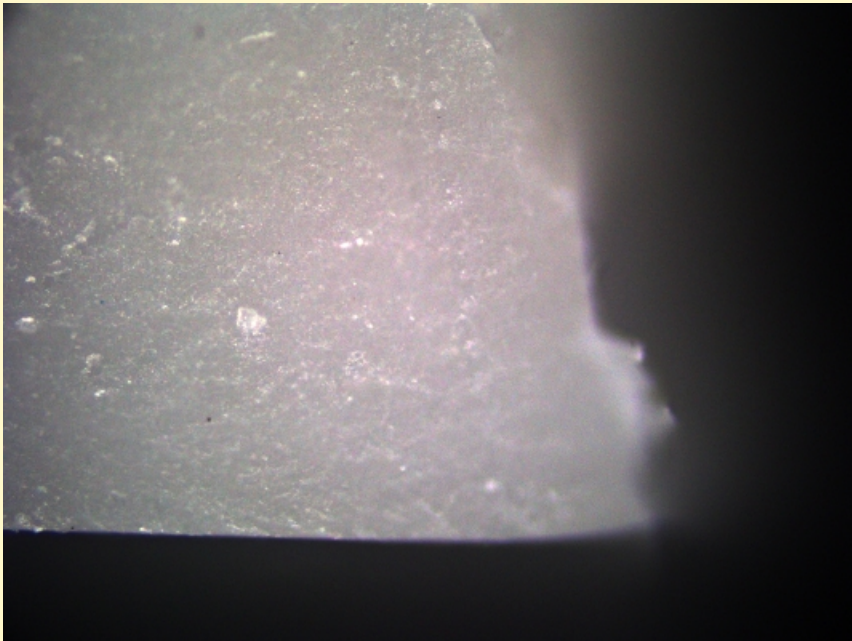
Delrin 127 UV



Study of plasma effects on various materials

- 2 hrs. of H₂ plasma @ 50 Watts
- All images 100x

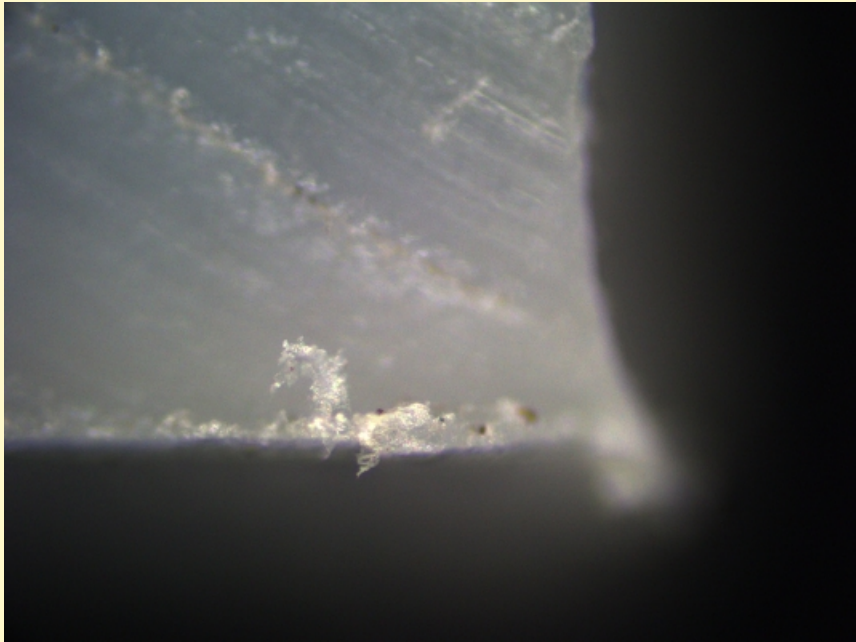
Delrin 527 UV



Study of plasma effects on various materials

- 2 hrs. of H₂ plasma @ 50 Watts
- All images 100x

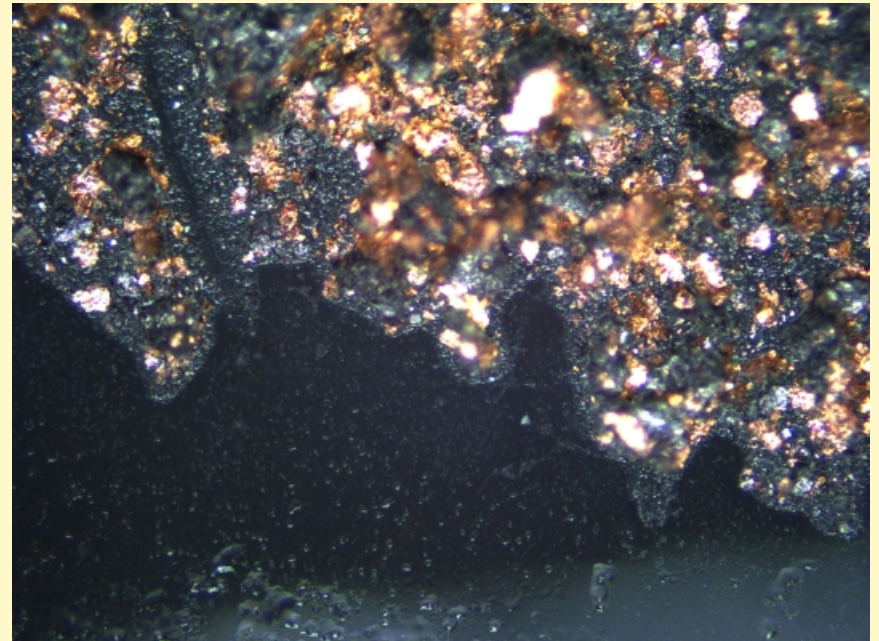
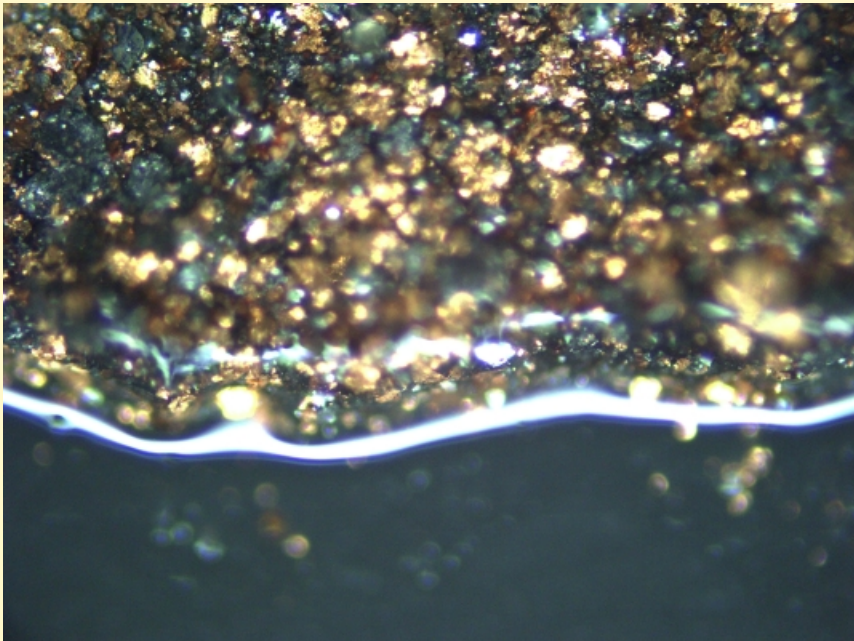
UHMW-P



Study of plasma effects on various materials

- 2 hrs. of H₂ plasma @ 50 Watts
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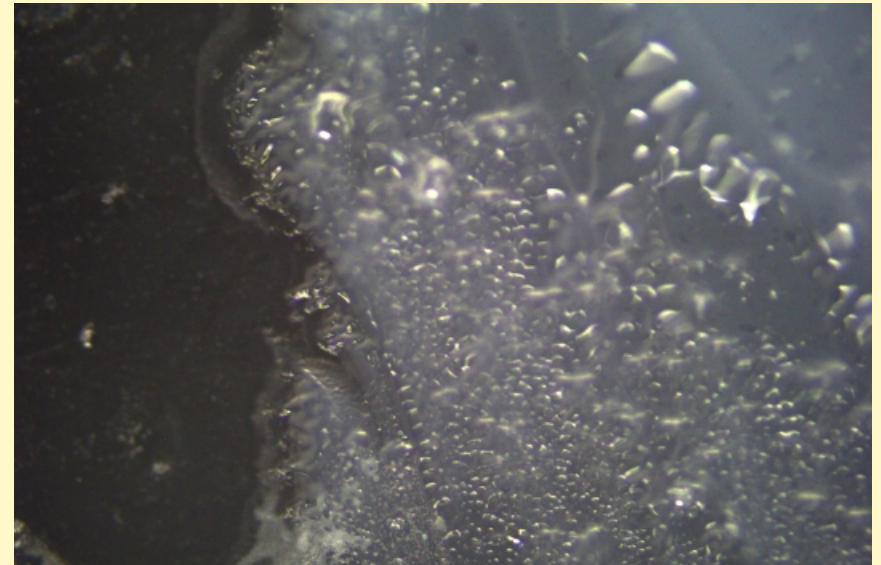
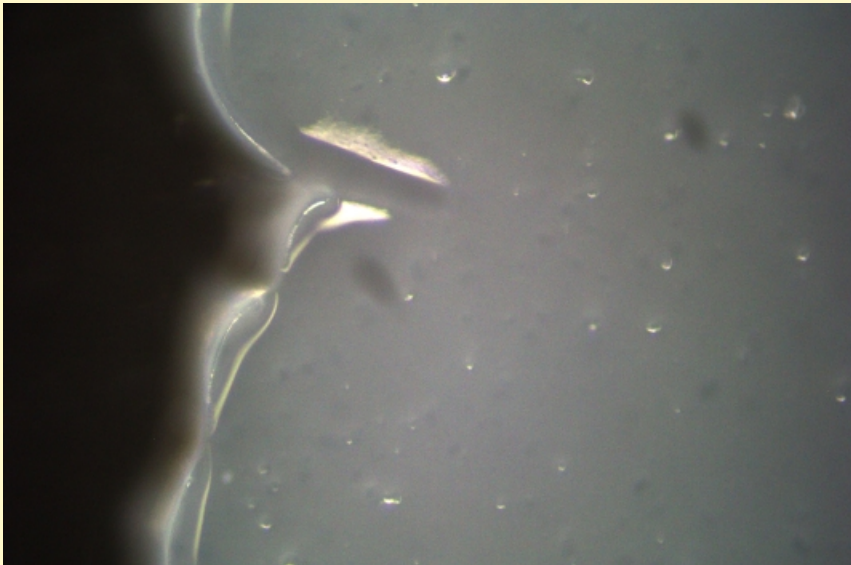
C5-A



Study of plasma effects on various materials

- 2 hrs. of H₂ plasma @ 50 Watts
- All images 100x

Nye 6300

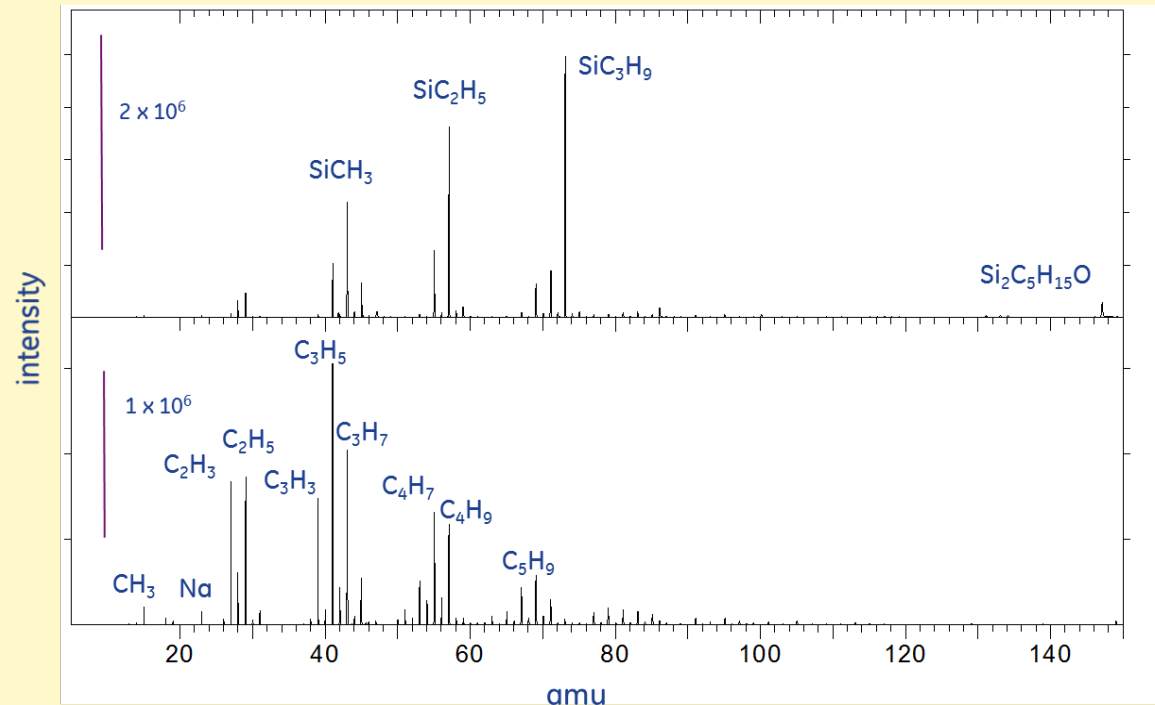


Recent result (using N2-O2 plasma)

- Plasma removal of PDMS* silicone from paper coupon using ToF-SIMS

Prior to
plasma
exposure

After 20 min.
and 10 W
plasma
exposure

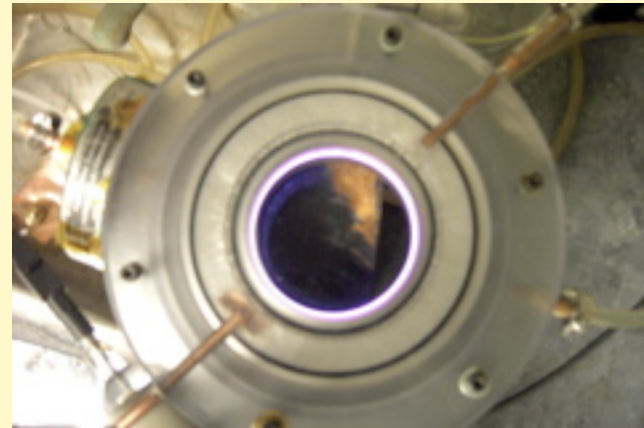
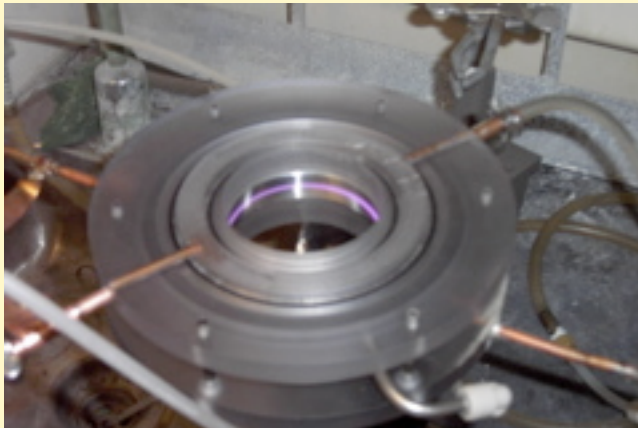


*- polydimethylsiloxane



Future directions

- Alternative gas chemistries (e.g., Ruzic @ Illinois, e.g. *J. Vac. Sci. Technol. B 31(1), Jan/Feb 2013*)
- Localized cleaning systems for optical elements
 - TEM wand
 - Prior work (1): Circular plasma

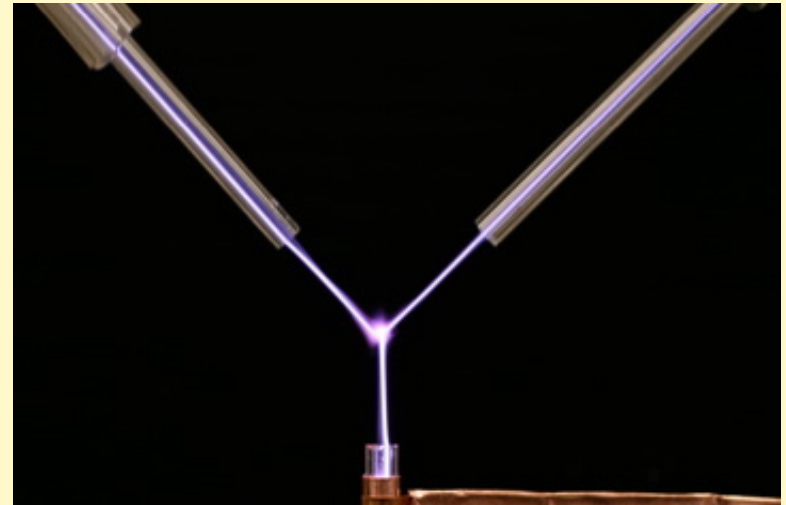
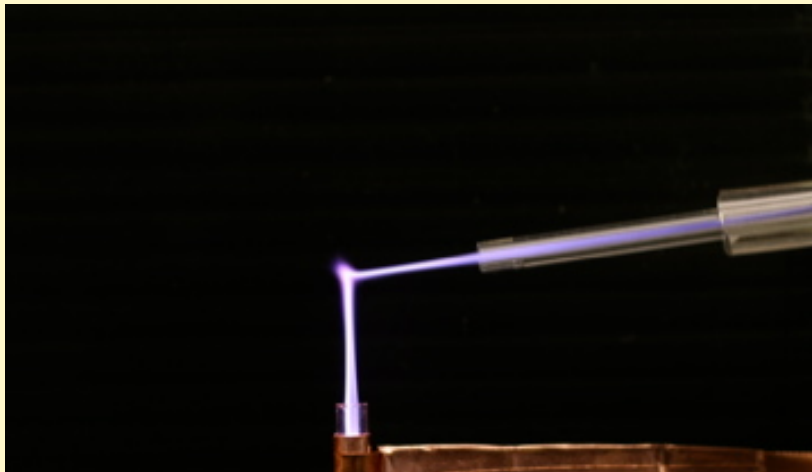


Future directions (continued)

- Prior work (2): Needles/jets



- Can be *arrayed*



Conclusions

- New electrode design capable of 50 W plasma power (> 150 W in limited tests)
- For both air (O_2 - N_2) and hydrogen (H_2) it was found that gas pressure selection is a key for maximizing cleaning rates
- Higher pressures increase scattering by the gas
- Lower pressures required to reach farther
 - Reduced pressure smaller effect on reactant concentration (since $N_{\text{gas}} \gg n_{\text{electron}}$)
- A stable method for hydrocarbon film preparation allows for parametric studies of plasma cleaning
- Material removal can affect more than just typical hydrocarbons

